





Overview and latest updates of PSP and L-UTSOI standard model



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W5: MOS-AK: Compact Modeling Support for OpenPDK and FOSS IC Designs









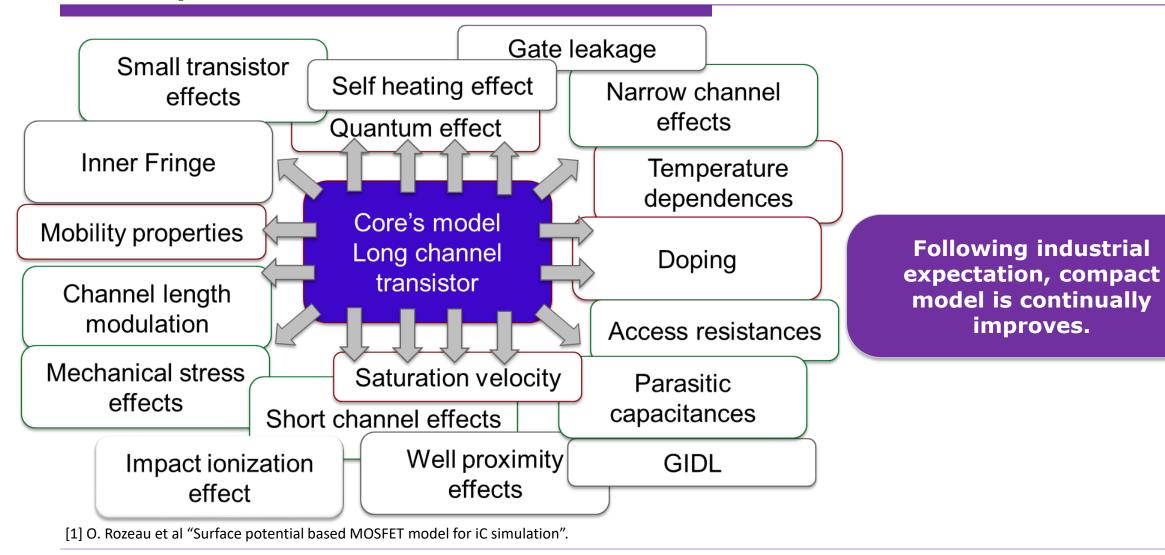
Outline



- □ Introduction
- □ PSP 104.0 new non backward compatible model
 - Summary of PSP version
 - PSP104 Revise OP-output
 - PSP104 Vdsat for long channel
 - PSP104 Improved symmetry for low AX value
 - PSP104 Improved Q-model in short channels
- L-UTSOI recent feature:
 - Summary of L-UTSOI version
 - L-UTSOI Computational Cryo issue & solution
 - Introduction of band edge defects
 - Cryo.: some illustrations
 - Leakages induced by edge transistors
 - Q-model decoupling
- Conclusion







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From equation to "standard model": CMC

☐ Why do we need device's model (MOSFET, Bipolar ...)?



- ☐ What does "standard model" means?
 - ☑ Continual Improvement ☑ Quality Assurance
- ☑ EDA tools Availability
- Why do we need CMC (Compact Model Coalition)?
 - ☑ Standarization process management
- Worlwide collaborative working groups
- ☑ IC Manufacturers / EDA editors / Model developers

■ Who are the developers around the world (transistor)?

<u>Transistor Model:</u> * MOSFET-like model; ** Bipolar; *** Power model Other model is dvp. By CMC (diode, ESD ...)





Outline

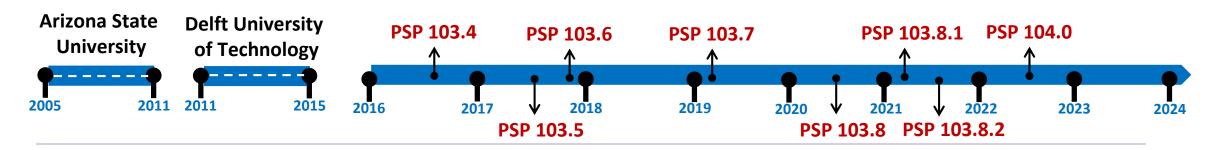


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PSP model



- □ PSP is a surface potential based model for deep-submicron bulk MOSFET.
 JUNCAP is a diode models part of PSP package.
- In December 2005, PSP has been elected a new industrial standard model by the CMC. This initial version was based on MM11 (from NXP Semiconductors) and SP (from Pennsylvania State University and later at Arizona State University).
- PSP meets numerical requirements for Digital, Analog-Mixed Signal, and RF circuit designs, in particular continuous derivation of currents and charges is insured.
- ☐ Since 2015 CEA-LETI is in charge of model update.







	Date	Release PSP	Major improvements/features
	08/2016	103.4	 Update JUNCAP 200.5 Add SWEDGE for edge transistor. Add SWIGN for induced gate noise. Add short channel effect (PSCE).
	08/2017	103.5	- Introduction of exponent dependence of CS (THECS).
	12/2017	103.6	- Introduction of non-uniform DIT.
	02/2019	103.7	Introduction of new parameter for gate leakage current.Add SWQPART for charge partitioning between source and drain.
	07/2020	103.8	Introduction of inner fringe charge model.Introduction of extra overlap charge model.
	04/2021	103.8.1	Update JUNCAP 200.6TRISE, DTEMP and TREF.
	06/2022	103.8.2	- Add SWFIX for fix non physical behavior.
	09/2023 104.0		 5th model version including JUNCAP 200.6. New DIBL model based on quasi-fermi level correction including screening effect in inversion. Add new parameter to improve gm description in saturation: THESATT. Capacitance reciprocity improvement using CTG/CTB parameters. New calculation of the drain saturation voltage for long channel transistor. Improvement of S/D symmetry with introduction of new linear-saturation transition. Remove effective doping bias-dependence effect: VSUB, NSLP, DNSUB. New binning equation with "hybrid" approach. Revised DC operating output.

Presentation today focus on the last release



PSP104 - Revise OP-output

Motivations:

- Reduce the number of .OP variables (256 in PSP103 -> 101 in PSP104)
- Updated list of .OP variables provided by the WG members (STM, NXP)
- Configurable OP information with switches:
 - □ Convention (SWOPPMOS flag):
 - PMOS \rightarrow All voltages and currents have signs related to the circuit simulation (e.g. pmos Vth is negative)
 - NMOS → All voltages and currents are represented as for nmos (cf. PSP103)
 - □ S/D interchange (SWOPDRAIN flag):
 - The drain is considered to be the electrical drain (e.g. Vds is always positive for nmos)
 - The drain is considered to be the first terminal of the model in a netlist
 - ☐ Effects of access resistances (SWOPREXT flag):
 - OP variables include the impact of Rd/Rg/Rs
 - OP variables don't include the impact of Rd/Rg/Rs



PSP104 - Vdsat for long channel 1/2

☐ Saturation drain voltage in PSP103

Considering the equation of the channel current without saturation velocity effect:

$$\begin{split} I_d &= -\frac{W}{L_{eff}} \cdot C'_{ox} \cdot \mu_{eff} \cdot \left(\left(q_{i,s} + \alpha \cdot \varphi_T \right) \cdot \psi_{ds} - \frac{\alpha}{2} \cdot {\psi_{ds}}^2 \right) \\ \text{and using the condition: } \left. \frac{\partial I_d}{\partial x_{ds}} \right|_{\psi_{ds} = \psi_{inf}} = 0 \end{split}$$



$$\psi_{\rm inf} = \frac{q_{\rm i,s}}{\alpha} + \Phi_{\rm T}$$

□ Saturation drain voltage in PSP104

Another condition, valid in all regimes, is considering the Poisson's equation and the boundary conditions:

Simp. SP
$$(V_g - \psi_d)^2 = G_f^2 \cdot \left(\psi_d - \Phi_T - \Phi_T \cdot \exp\left(\frac{\psi_d - V_{db}}{\Phi_T}\right)\right)$$
 Negligible in saturation



$$\psi_{inf} = \Phi_{T} \cdot a_{sat} \cdot \left(1 - \sqrt{1 - \frac{G_{f}^{2} \cdot exp\left(\frac{\psi_{s} - V_{sb}}{\Phi_{T}}\right)}{a_{sat}^{2}}}\right)$$



PSP104 - Vdsat for long channel 2/2

Improve the accuracy of drain current in saturation for long channel MOSFET.

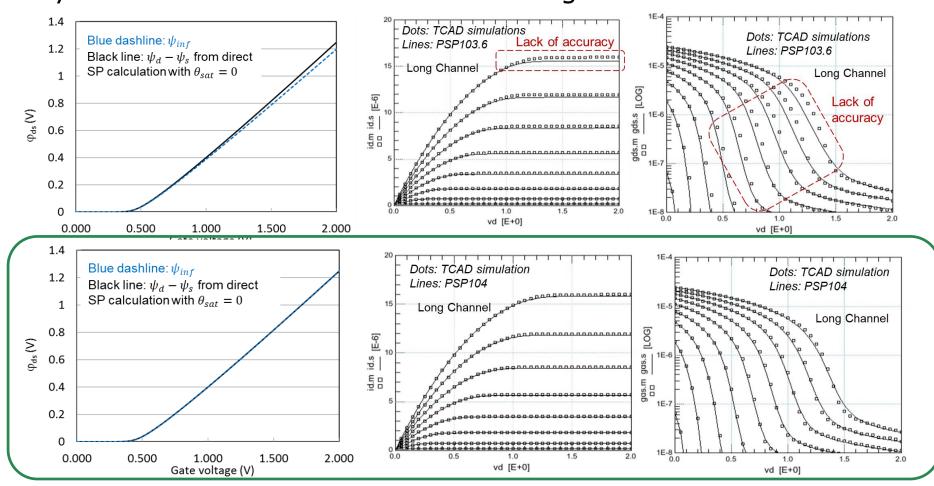
PSP 103:

VDSAT for long channel used derivative condition

$$\left. \frac{\partial I_d}{\partial x_{ds}} \right|_{\psi_{ds} = \psi_{inf}} = 0$$

PSP 104:

Solved by the use of a new calculation sequence of Vdsat



PSP104 - Improved symmetry for low AX value

- \square PSP 103 limitation: V_{dse} function is not $C\infty$ in regards to Gummel test for low AX-value
- PSP104: use a new mathematical function with C∞ function (from K. Xia et al. TED 2020)

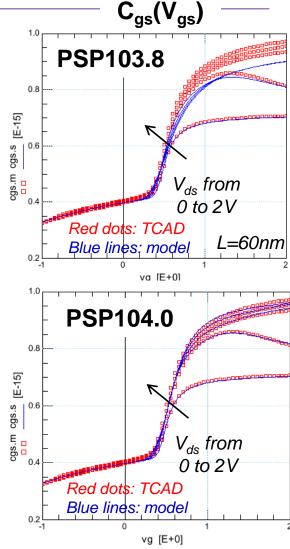
$$PSP \ 103 \ v_{dse} = \frac{v_{ds}}{\left(1 + \left(\frac{V_{ds}}{V_{dssat}}\right)^{4X}\right)^{4X}} \qquad PSP \ 104 \ v_{dse} = \frac{2.\sqrt{1 + AR}.V_{ds}}{\sqrt{\left(\frac{\sqrt{1 + AR}.V_{ds}}{V_{dssat}} - 1\right)^2 + AR}} \ w. \ AR = \frac{\left(\frac{(2)^{-\frac{2}{AX}} - 1}{2.(2)^{-\frac{2}{AX}} - 1}\right)^2}{2.(2)^{-\frac{2}{AX}} - 1} \ AR = 10, 1, 0.2, 0.05, 0.001, 0$$

$$AR = 10, 1,$$

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PSP104 - Improved Q-model in short channels

- Motivation: PSP 103.0 Q-model's limitation in short channel
 - Artefact on CV in accumulation induced by DIBL model: requires to set CFAC=0
 - Underestimation of V_{DSAT} for CV: requires THESATAC<THESAT
 - The lin-sat transition on CV is smoother compared to the one of IV: requires AXAC<AX</p>
 - Partial depletion of overlaps: Cgd is overestimated in saturation. Requires a "negative" CLM
- ☐ For PSP104.0.0 release:
 - Revisited DIBL model
 - Addition of flexibility on CLM parameters (ALP can be negative) for Q-model
 - No new parameters for users



Outline

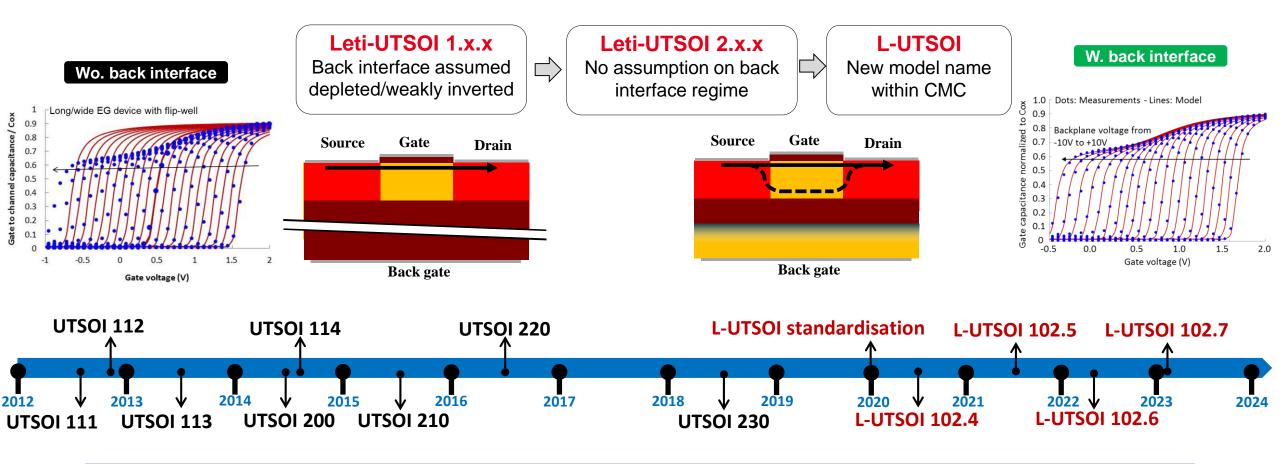


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L-UTSOI model



□ L-UTSOI is a surface potential based model dedicated to FDSOI technology.



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Summary of L-UTSOI version

Date	Release L-UTSOI	Major improvements/features	
01/2020	102.4	Introduction of impact ionization model (Samsung request).Introduction of extra gate to overlap current (STm request).	
01/2021	102.5	Introduction of Gate Poly-Depletion model (Qualcomm request).Enhancement of substrate depletion (STm request).	
03/2022	102.6	- Introduction of RTA NOS model (Samsung request).	
02/2023	102.7	- Introduction of cryogenic model (All request).	
06/2024	102.8	Introduction of edge transistor (Samsung request).Charge decoupling for RF application (Samsung request).	

Presentation today focus on the last release

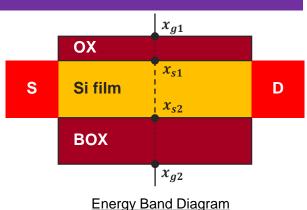


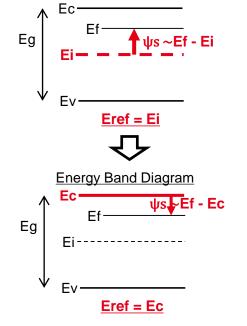
L-UTSOI Computational Cryo & solution 1/2

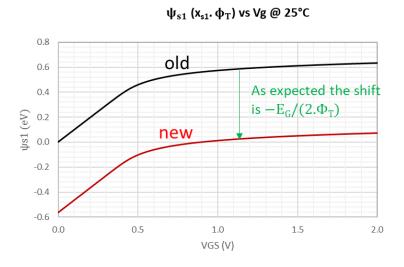
L-UTSOI SPE:

$$\begin{cases} q^{2} = k_{1}^{2} (x_{g1} - x_{s1})^{2} - A_{0} e^{x_{s1}} e^{-x_{n}} \\ q^{2} = k_{2}^{2} (x_{g2} - x_{s2})^{2} - A_{0} e^{x_{s2}} e^{-x_{n}} \\ \frac{q}{2} + \coth^{-1} \left(\frac{k_{1} (x_{g1} - x_{s1})}{q} \right) - \coth^{-1} \left(\frac{k_{2} (x_{g2} - x_{s2})}{q} \right) = 0 \end{cases}$$

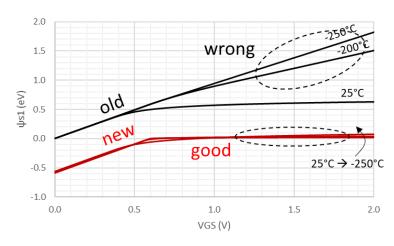
	L-UTSOI 102.6	L-UTSOI 102.7
Energy Reference	E_i	E_c
$A_0 \propto n_0$	$\sqrt{N_C N_V} e^{-\frac{E_g}{2k_B T}}$	$\propto \sqrt{N_C N_V}$
$oldsymbol{x_{S1}}{ ext{(strong inversion)}}$	$\sim \! rac{E_g}{2k_BT}$	~0
$\lim_{T\to 0} A_0 e^{x_{s1}}$	$0 \times \infty = ?$	$\sqrt{N_C N_V}$







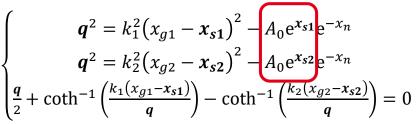
 ψ_{s1} (x_{s1}. φ_T) vs Vg @ 25, -200°C & -250°C



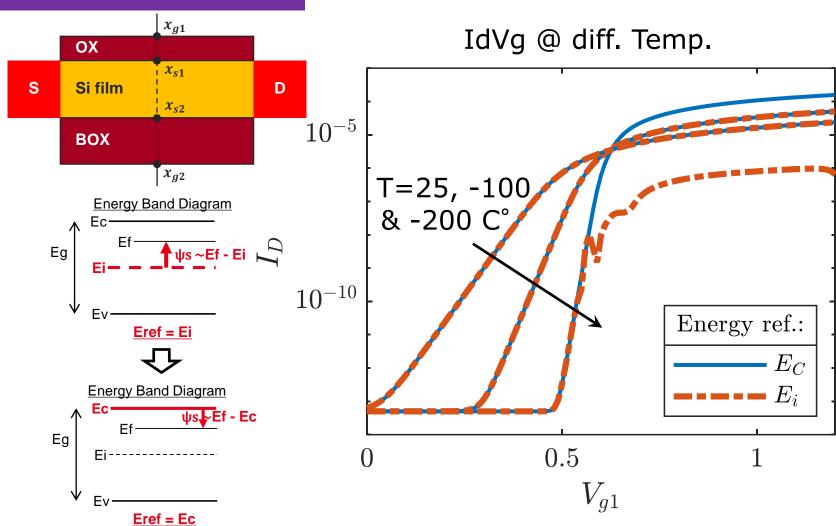


L-UTSOI Computational Cryo & solution 2/2

L-UTSOI SPE:



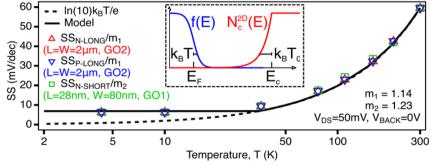
	L-UTSOI 102.6	L-UTSOI 102.7
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$A_0 \propto n_0$	$\sqrt{N_C N_V} e^{-\frac{E_g}{2k_B T}}$	$\propto \sqrt{N_C N_V}$
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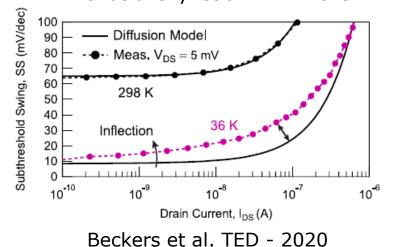


Introduction of band edge defects

SS Saturation as the temperature decreases. Mechanism: Localized Band tail states acting as interface traps.

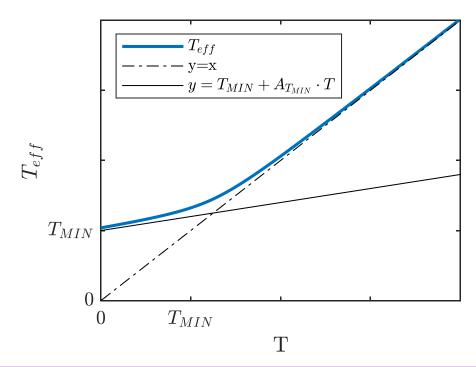


H. Bohuslavskyi et al EDL - 2019



L-UTSOI: implementation temperature pinning:

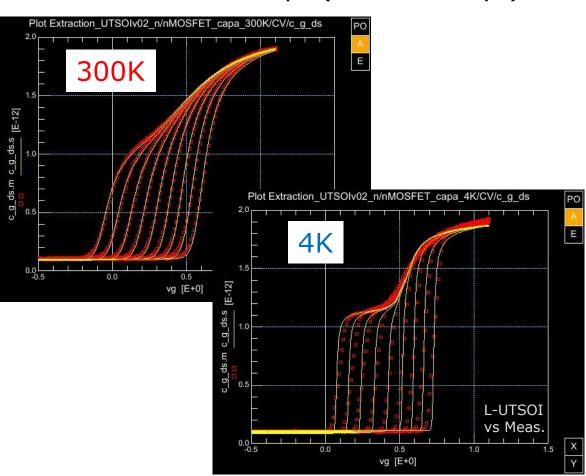
$$T_{eff} = \frac{T + T_0 + \sqrt{(T - T_0)^2 + B_{T_{MIN}}^2}}{2} \text{ w. } T_0 = T_{MIN} + A_{T_{MIN}} \cdot T$$



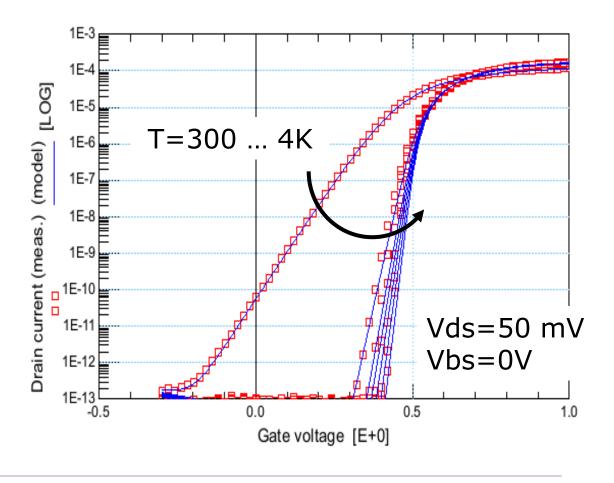


Cryo.: some illustrations

C-V @ diff. Temp. (mod. Vs exp.)



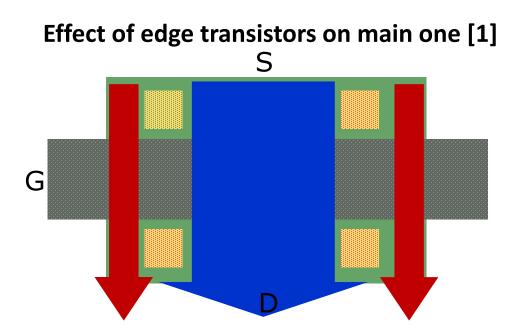
IdVg @ diff. Temp. (mod. Vs exp.)

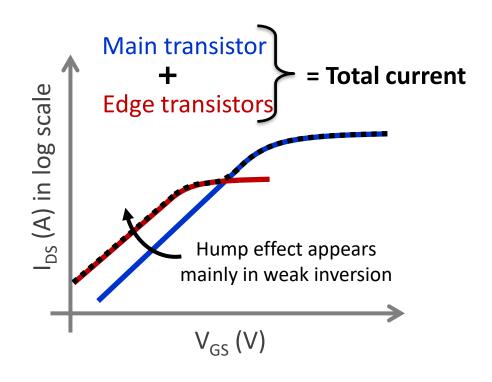




EDGE transistor

Parasitic edge transistor is well known in bulk MOSFET





[1] K. Sakakibara et al. JJAP, May 2014.



Leakages induced by edge transistors 1/3

Short model description

Goal: accurate model in weak and moderate inversions with limited degradation of the CPU run-time

Charge calculation

$$\begin{cases} q_{i} = q_{i,WI0} \cdot e^{-q_{i}} \cdot e^{-x_{n}} \\ q_{i} = \mathcal{W}_{0} \left(\frac{q_{i,WI0} \cdot e^{-x_{n}}}{\text{nfactor}} \right) \end{cases}$$

Simplified channel current calculation

$$I_{d} = -I_{d0} \left[\frac{1}{2} (q_{i,d}^{2} - q_{i,s}^{2}) + (q_{i,d} - q_{i,s}) \right]$$

with: $I_{do} = \frac{W}{I_{do}} \cdot C'_{ox} \cdot \mu_{eff} \cdot \phi_{T}^{2}$

Notice: V_{dsat} is the one of main transistor

Id vs Vg @ Vd=50mV for Vb=-2 .. 2V with or without edge transistor

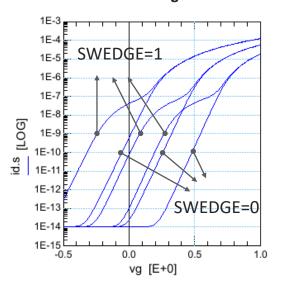
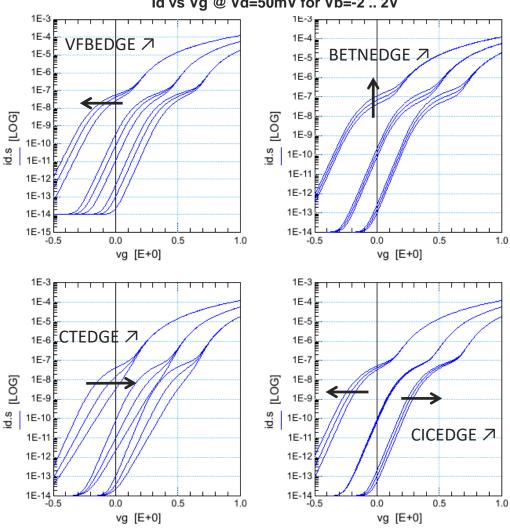


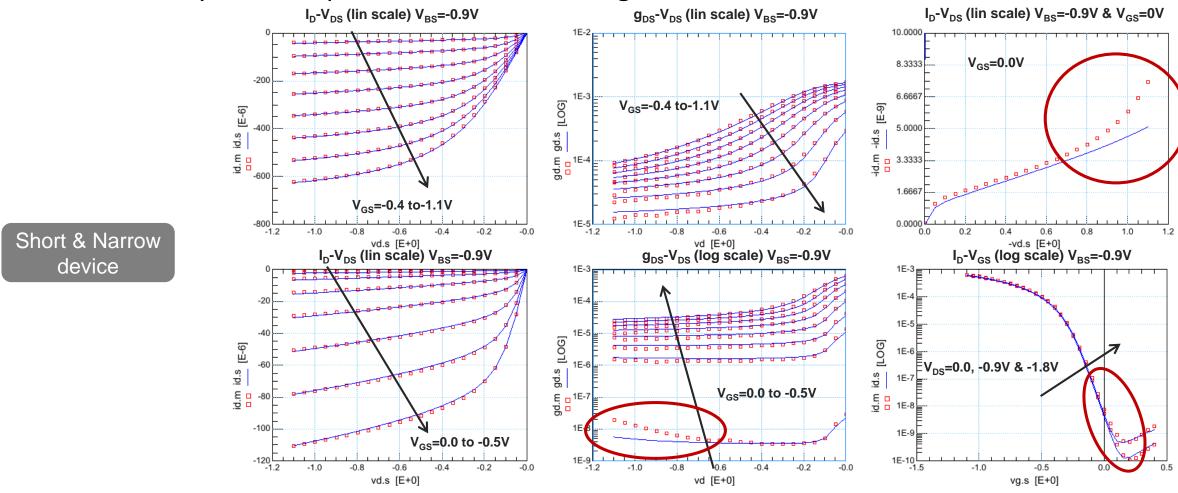
Illustration of model parameters effects Id vs Vg @ Vd=50mV for Vb=-2 .. 2V





Leakages induced by edge transistors 2/3

Issue: difficulty to fit experimental data at negative Vbs

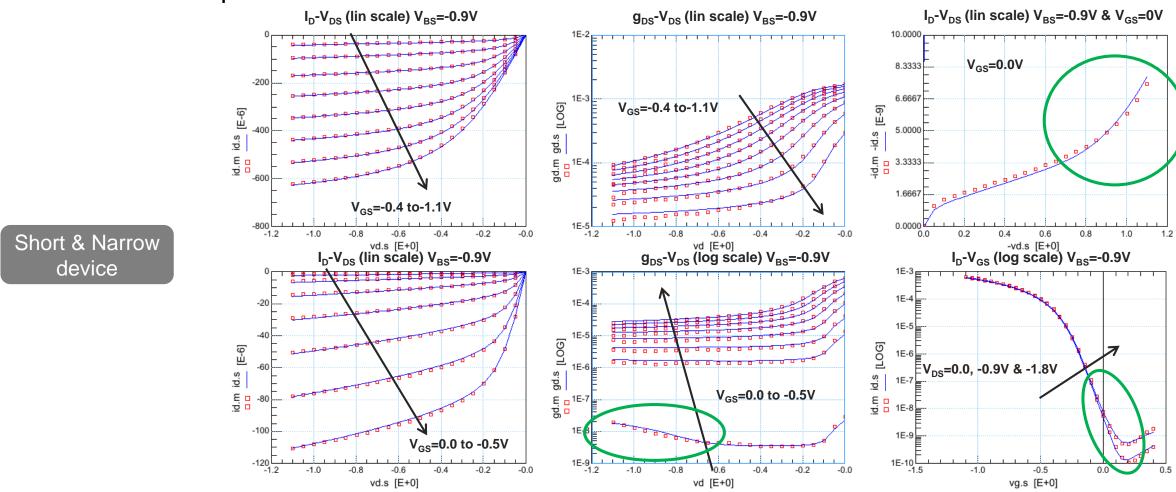


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Leakages induced by edge transistors 3/3

Validation on experimental data



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Q-model decoupling

- ☐ Issue: Q-model shows accuracy limitations in saturation regime for short channel transistors.
- Solution for L-UTSOI 102.8:
 - Introduction of new switch SWQMOD for Q-model decoupling.
 - Addition of new model parameters dedicated to Q-model
 - This solution requires significant code changing (charges are calculated twice when Q-model decoupling is activated)

Q-model decoupling is activated if SWQMOD=1 Source/drain SP calculation using standard parameters (VFB, PSCE, CF, THESAT, etc.) SWQMOD=1 2nd source/drain SP calculation using new AC parameters (VFBAC, PSCEAC, SWQMOD=0 CFAC, THESATAC, etc.) Currents calculation Charges calculation (AC) (DC)

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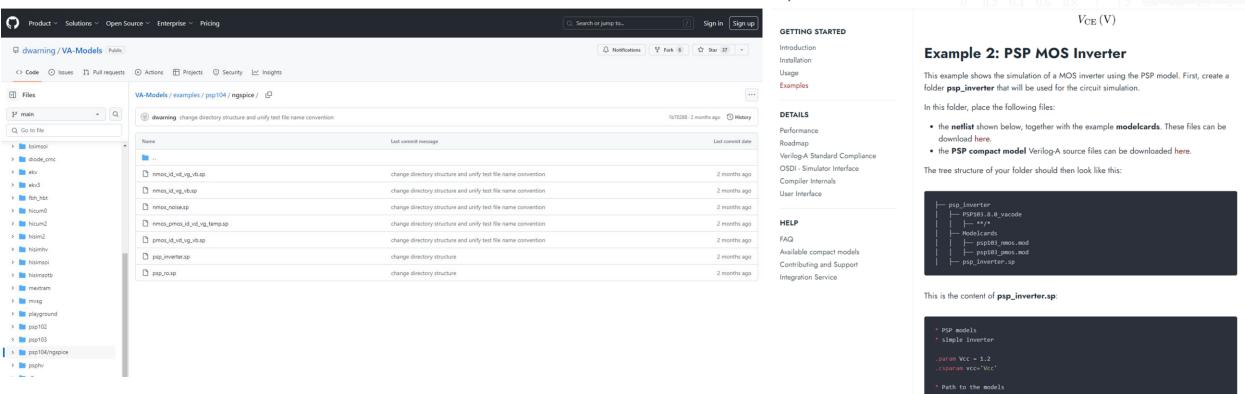


□ Here some example of input file using PSP or L-UTSOI with code: https://github.com/dwarning/VA-Models/tree/main/examples we would to thanks the participants of these websites

OpenVAF Docs Downloads Blog

■ Here OPEN VAF website with PSP example:

https://openvaf.semimod.de/docs/getting-started/examples/



Search docs

Conclusion: Compact modeling @ CEA-LETI



- □ Our team is a developer of the CMC (Compact Model Coalition) for 2 SPICE models: standardization process, implementation in commercial IC simulators, strong interaction with users.
 - L-UTSOI compact model is dedicated to FDSOI technologies:

https://www.cea.fr/cea-tech/leti/l-utsoisupport

□ PSP is a surface potential based model for deep-submicron bulk MOSFET:

https://www.cea.fr/cea-tech/leti/pspsupport

- Our website contains: Release information, Model documentation for PSP and L-UTSOI and Downloadable Verilog-A codes.
- Acknowledgement: Gert-J. Smit (NXP), A. Scholten (NXP), H. Lee (Samsung), P. Scheer (ST) and all people that gives us feedback on our models to improve it.
- □ Code are also available through CMC link: https://si2.org/download-links/
- □ <u>L-UTSOI paper in ESSERC:</u> "Cryogenic L-UTSOI Model for 22nm pMOS FD-SOI, Including Stress Effects", Miltiadis Alepidis, Sylvie Jarjayes, Thomas Bédécarrats, Sébastien Martinie, Mikaël Cassé, Christian Witt, Olivier Rozeau.

Merci/thanks





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PSP104 - Improved binning rules

- New binning equations for PSP104: "hybrid" approach
 - New generic binning equation template

$$YYY = f_{scaling} \cdot \left(POYYY + PLYYY \cdot \frac{L_{EN}}{L_{E}} + PWYYY \cdot \frac{W_{EN}}{W_{E}} + PLWYYY \cdot \frac{L_{EN}}{L_{E}} \cdot \frac{W_{EN}}{W_{E}} \right)$$

Equation: type I

 $f_{scaling}$ captures the dominant first order scaling trend (differs between parameters). Binning rule is always type-I

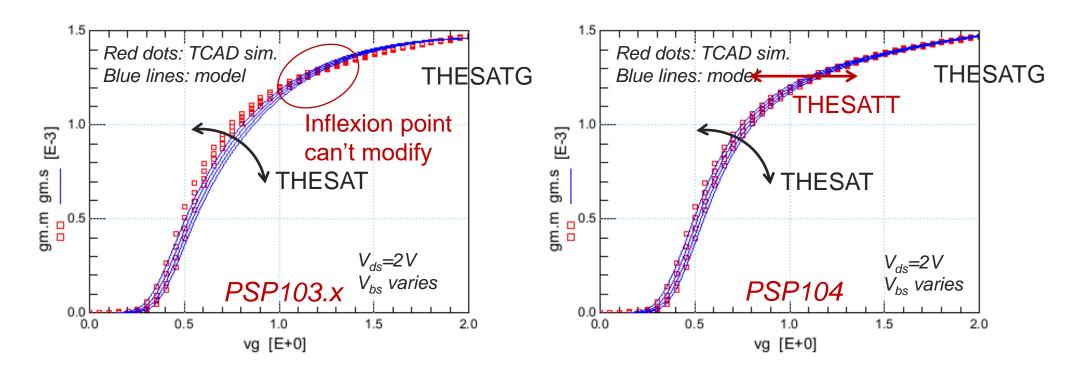
Examples:
$$ALP = \frac{L_{EN}}{L_E} \cdot \left(POALP + PLALP \cdot \frac{L_{EN}}{L_E} + PWALP \cdot \frac{W_{EN}}{W_E} + PLWALP \cdot \frac{L_{EN}}{L_E} \cdot \frac{W_{EN}}{W_E} \right)$$

$$IGINV = \frac{L_E \cdot W_E}{L_{EN} \cdot W_{EN}} \cdot \left(POIGINV + PLIGINV \cdot \frac{L_{EN}}{L_E} + PWIGINV \cdot \frac{W_{EN}}{W_E} + PLWIGINV \cdot \frac{L_{EN}}{W_E} \cdot \frac{W_{EN}}{W_E} \right)$$



PSP104 - Improvement of G_m in saturation

- ☐ Issue: need flexibility to adjust gm in saturation
- Solution for PSP104: introduce a new parameter (THESATT) to adjust gate bias dependence of V_{DSAT}





Definition for low temp: generic example

